

100318690

531 Rec'd PCT 20 DEC 2001

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
CHIBA, Tatsuo, et al. ) Atty. Docket No.: TSUK 0005  
Serial No. \_\_\_\_\_ (corresponding to )  
PCT/JP00/04028 filed 21 June 2000) )  
Filed: Herewith )  
For: PHOTSENSITIVE ELEMENT, )  
PHOTSENSITIVE ELEMENT ROLL, )  
PROCESS FOR THE PREPARATION )  
OF RESIST PATTERN USING THE )  
SAME, RESIST PATTERN, RESIST )  
PATTERN LAMINATED )  
SUBSTRATE, PROCESS FOR THE )  
PREPARATION OF WIRING ) Date: 20 December 2001  
PATTERN AND WIRING PATTERN )

5/A  
D.G.  
3-12-02

PRELIMINARY AMENDMENT (A)

BOX: PCT (DO/EO/US)  
Assistant Commissioner for Patents  
Washington, D. C. 20231

Sir:

Prior to calculating the filing fee, kindly amend the above-captioned application as follows:

IN THE CLAIMS:

Kindly amend claims 20, 22, 29-31 and 40 and replace them with the following:

A1  
20. (Amended) A photosensitive element roll according to Claim 1, wherein the above photosensitive element is wound up or rolled around a core.

A2  
22. (Amended) A process for preparing a resist pattern which comprises laminating the photosensitive element according to Claim 1 to a substrate for forming a circuit so that the photosensitive resin composition layer is closely contacted to the substrate, irradiating imagewise active light to photocure the exposed portion, and removing an unexposed